11/14/2017 504641354

PATENT ASSIGNMENT COVER SHEET

Electronic Version v1.1 Stylesheet Version v1.2

EPAS ID: PAT4688074

SUBMISSION TYPE:	NEW ASSIGNMENT
NATURE OF CONVEYANCE:	ASSIGNMENT

CONVEYING PARTY DATA

Name	Execution Date
SORAA, INC.	09/08/2017

RECEIVING PARTY DATA

Name:	SLT TECHNOLOGIES, INC.
Street Address:	C/O LOEB & LOEB
Internal Address:	10100 SANTA MONICA BLVD., SUITE 2200
City:	LOS ANGELES
State/Country:	CALIFORNIA
Postal Code:	90067

PROPERTY NUMBERS Total: 1

Property Type	Number
Application Number:	15469196

CORRESPONDENCE DATA

Fax Number: (713)623-4846

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Correspondent Name: PATTERSON & SHERIDAN LLP

Address Line 1: 24 GREENWAY PLAZA

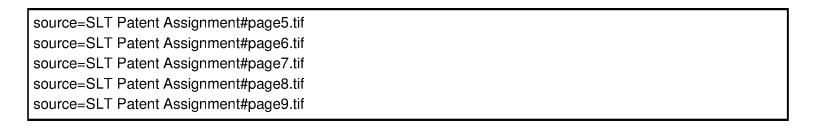
Address Line 2: **SUITE 1600**

Address Line 4: HOUSTON, TEXAS 77046

ATTORNEY DOCKET NUMBER:	15469196
NAME OF SUBMITTER:	JOSEPH J. STEVENS
SIGNATURE:	/Joseph J. Stevens/
DATE SIGNED:	11/14/2017

Total Attachments: 9

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PATENT ASSIGNMENT AGREEMENT

This PATENT ASSIGNMENT AGREEMENT ("Patent Assignment"), dated as of September 22, is made by Soraa, Inc. ("Seller"), a Delaware corporation, in favor of SLT Technologies, Inc. ("Buyer"), a Delaware corporation, the purchaser of certain assets of Seller pursuant to an Asset Purchase Agreement dated as of September 8, 2017 (the "Asset Purchase Agreement").

WHEREAS, under the terms of the Asset Purchase Agreement, Seller has agreed to sell, convey, transfer, assign, and deliver to Buyer, among other assets, certain patents and patent applications of Seller, and has agreed to execute and deliver this Patent Assignment, for the purpose of recording the assignment with the United States Patent and Trademark Office and the corresponding patent offices, entities or agencies in any applicable jurisdiction (including any applicable foreign country);

NOW THEREFORE, in accordance with the Asset Purchase Agreement and in consideration of the promises and covenants contained herein and therein, the parties agree as follows:

- 1. <u>Assignment</u>. For good and valuable consideration, the receipt and sufficiency of which are hereby acknowledged, Seller hereby irrevocably sells, conveys, transfers, assigns, and delivers to Buyer, and Buyer hereby accepts, all of Seller's right, title, and interest in and to the following (the "Assigned Patents"):
- (a) the patents and patent applications set forth in Schedule 1 hereto and all issuances, divisions, continuations, continuations-in-part, reissues, extensions, reexaminations, and renewals thereof:
- (b) all rights of Seller accruing under any of the foregoing provided by applicable law of any jurisdiction, by international treaties and conventions, and otherwise throughout the world;
- (c) any and all royalties, fees, income, payments, and other proceeds now or hereafter due or payable with respect to any and all of the foregoing; and
- (d) any and all claims and causes of action based on any of the foregoing, whether accruing before, on, or after the date hereof, including all rights to and claims for damages, restitution, and injunctive and other legal and equitable relief for past, present, and future infringement, misappropriation, violation, misuse, breach, or default, with the right but no obligation to sue for such legal and equitable relief and to collect, or otherwise recover, any such damages.
- 2. Recordation and Further Actions. Seller hereby authorizes the Commissioner for Patents in the United States Patent and Trademark Office and the officials of corresponding patent offices, entities or agencies in any applicable jurisdiction (including any applicable foreign country) to record and register this Patent Assignment upon request by Buyer. Following the date hereof, upon Buyer's reasonable request, Seller shall take such reasonable steps and actions, and provide such reasonable cooperation and assistance to Buyer and its successors, assigns, and legal representatives, including the execution and delivery of any affidavits, declarations, oaths, exhibits, assignments, powers of attorney, or other documents, as may be reasonably necessary to effect, evidence, or perfect the assignment of the Assigned Patents to Buyer, or any assignee or successor thereto.
- 3. Terms of the Asset Purchase Agreement. The parties hereto acknowledge and agree that this Patent

Assignment is entered into pursuant to the Asset Purchase Agreement, to which reference is made for a further statement of the rights and obligations of Seller and Buyer with respect to the Assigned Patents. The representations, warranties, covenants, agreements, and indemnities contained in the Asset Purchase Agreement shall not be superseded hereby but shall remain in full force and effect to the full extent provided therein. In the event of any conflict or inconsistency between the terms of the Asset Purchase Agreement and the terms hereof, the terms of the Asset Purchase Agreement shall govern.

- 4. <u>Counterparts</u>. This Patent Assignment may be executed in counterparts, each of which shall be deemed an original, but all of which together shall be deemed one and the same agreement. A signed copy of this Patent Assignment delivered by facsimile, e-mail, or other means of electronic transmission shall be deemed to have the same legal effect as delivery of an original signed copy of this Patent Assignment.
- 5. <u>Successors and Assigns</u>. This Patent Assignment shall be binding upon and shall inure to the benefit of the parties hereto and their respective successors and assigns.
- 6. <u>Governing Law</u>. This Patent Assignment shall be governed by, and construed and enforced in accordance with, the laws of the State of California other than conflict of laws principles thereof directing the application of any law other than that of California.
- 7. <u>Entire Agreement</u>. This Patent Assignment and the Schedule attached hereto, together with the Asset Purchase Agreement, constitute the entire agreement between the parties with respect to the subject matter of this Patent Assignment and supersede all prior agreements and understandings, both oral and written, between the parties with respect to the subject matter of this Patent Assignment.

[Signature page follows]

IN WITNESS WHEREOF, the parties have duly executed and delivered this Patent Assignment as of the date first above written.

SORAA, INC.

Ву:

Name: Jeff Parker

Title: Chief Executive Officer

Address for Notices:

6500 Kaiser Drive, Suite 110 Fremont, CA 94555

SLT TECHNOLOGIES, INC.

Ву:_____

Name: Kenneth Benbassat

Title: Secretary

Address for Notices:

c/o Loeb & Loeb LLP 10100 Santa Monica Blvd., Suite 2200 Los Angeles, CA 90067

REEL: 044120 FRAME: 0847

IN WITNESS WHEREOF, the parties have duly executed and delivered this Patent Assignment as of the date first above written.

Ву:
Name: Jeff Parker
Title: Chief Executive Officer
Address for Notices:

6500 Kaiser Drive Fremont, CA 94555

SORAA, INC.

SLT TECHNOLOGIES, INC.

By: Kenneth Berland

Name: Kenneth Benbassat

Title: Secretary

Address for Notices:

c/o Loeb & Loeb LLP 10100 Santa Monica Blvd., Suite 2200 Los Angeles, CA 90067

SCHEDULE 1

ASSIGNED PATENTS

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TITLE	COUNTRY	STATUS	APPLN. NO.	FILING DATE	PATENT NO.	ISSUE DATE
HIGH PRESSURE APPARATUS AND METHOD	USA	Issued	12/133,364	6/5/2008	8,097,081	1/17/2012
FOR NITRIDE CRYSTAL GROWTH						
HIGH PRESSURE APPARATUS AND METHOD	USA	Issued	13/013,697	1/25/2011	8,871,024	10/28/2014
FOR NITRIDE CRYSTAL GROWTH						
HIGH PRESSURE APPARATUS AND METHOD	USA	Issued	13/343,563	1/4/2012	8,986,447	3/24/2015
FOR NITRIDE CRYSTAL GROWTH						
HIGH PRESSURE APPARATUS AND METHOD	Japan	Issued	2011-512644	6/4/2009	5536046	5/9/2014
FOR NITRIDE CRYSTAL GROWTH						
HIGH PRESSURE APPARATUS AND METHOD	USA	Issued	12/478,736	6/4/2009	8,303,710	11/6/2012
FOR NITRIDE CRYSTAL GROWTH						
HIGH PRESSURE APPARATUS AND METHOD	Japan	Issued	2014-088867	6/4/2009	6138724	5/12/2017
FOR NITRIDE CRYSTAL GROWTH						
HIGH PRESSURE APPARATUS AND METHOD	USA	Issued	13/556,105	7/23/2012	9,157,167	10/13/2015
FOR NITRIDE CRYSTAL GROWTH						
PROCESS FOR LARGE-SCALE	USA	Issued	12/534,844	8/3/2009	8,979,999	3/17/2015
AMMONOTHERMAL MANUFACTURING OF						
GALLIUM NITRIDE BOULES	TTG		14/500 225	1/1/0015	***************************************	~~~~~
PROCESS FOR LARGE-SCALE	USA	Rejected	14/599,335	1/16/2015		
AMMONOTHERMAL MANUFACTURING OF GALLIUM NITRIDE BOULES						
APPARATUS AND METHOD FOR SEED	USA	Issued	12/534,843	8/3/2009	8,430,958	4/30/2013
CRYSTAL UTILIZATION IN LARGE-SCALE	USA	issuea	12/554,845	8/3/2009	8,430,938	4/30/2013
MANUFACTURING OF GALLIUM NITRIDE						
PROCESS AND APPARATUS FOR	USA	Issued	12/534,857	8/4/2009	8,021,481	9/20/2011
LARGE-SCALE MANUFACTURING OF BULK	USA	issucu	1.2/334,037	0/4/2009	0,021,401	9/20/2011
MONOCRYSTALLINE						
GALLIUM-CONTAINING NITRIDE						
PROCESS AND APPARATUS FOR	USA	Issued	13/226,249	9/6/2011	8,444,765	5/21/2013
LARGE-SCALE MANUFACTURING OF BULK	OSM	133000	15/220,247	2/0/2011	0,447,700	3/21/2013
MONOCRYSTALLINE						
GALLIUM-CONTAINING NITRIDE						
PROCESS AND APPARATUS FOR GROWING A	USA	Issued	12/534,849	8/3/2009	8,323,405	12/4/2012
CRYSTALLINE GALLIUM-CONTAINING			, , , , , , , , , , , , , , , , , , , ,		.,,	
NITRIDE USING AN AZIDE MINERALIZER						
NITRIDE CRYSTAL WITH REMOVABLE	USA	Issued	12/546,458	8/24/2009	8,148,801	4/3/2012
SURFACE LAYER AND METHODS OF					, ,	
MANUFACTURE						
NITRIDE CRYSTAL WITH REMOVABLE	USA	Issued	13/425,304	3/20/2012	8,329,511	12/11/2012
SURFACE LAYER AND METHODS OF						
MANUFACTURE						
LARGE-AREA SEED FOR	USA	Issued	12/556,558	9/9/2009	7,976,630	7/12/2011
AMMONOTHERMAL GROWTH OF BULK						
GALLIUM NITRIDE AND METHOD OF						
MANUFACTURE						
AMMONOTHERMAL METHOD FOR GROWTH	USA	Issued	13/175,739	7/1/2011	8,465,588	6/18/2013
OF BULK GALLIUM NITRIDE						
POLYCRYSTALLINE GROUP III METAL	China	Issued	200980154756.9	12/11/2009		5/13/2015
NITRIDE WITH GETTER AND METHOD OF					756.9	
MAKING						
POLYCRYSTALLINE GROUP III METAL	Japan	Issued	2011-540937	12/11/2009	5476637	2/21/2014
NITRIDE WITH GETTER AND METHOD OF						
MAKING					******	********
POLYCRYSTALLINE GROUP III METAL	USA	Issued	12/634,665	12/9/2009	8,461,071	6/11/2013
NITRIDE WITH GETTER AND METHOD OF						
MAKING		<u> </u>	<u></u>	<u> </u>		

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POLYCRYSTALLINE GROUP III METAL	USA	Issued	13/894,220	5/14/2013	8,987,156	3/24/2015
NITRIDE WITH GETTER AND METHOD OF						
MAKING	~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~	-				
POLYCRYSTALLINE GROUP III METAL	USA	Pending	15/469,196	3/24/2017		
NITRIDE WITH GETTER AND METHOD OF					array .	
MAKING	******************		***************************************			
LARGE-AREA BULK GALLIUM NITRIDE	USA	Issued	12/556,562	9/9/2009	8,048,225	11/1/2011
WAFER AND METHOD OF MANUFACTURE		-		<u> </u>		
HIGH PRESSURE APPARATUS WITH	USA	Issued	12/891,668	9/27/2010	8,435,347	5/7/2013
STACKABLE RINGS						
METHOD FOR SYNTHESIS OF HIGH QUALITY	USA	Issued	12/988,772	6/30/2011	9,175,418	11/3/2015
LARGE AREA BULK GALLIUM BASED			,			
CRYSTALS						
METHOD FOR SYNTHESIS OF HIGH QUALITY	USA	Pending	14/930,170	11/2/2015		
LARGE AREA BULK GALLIUM BASED	0,011	1 21101119	1,550,170	1 1, 2, 2 3 10		
CRYSTALS						
IMPROVED SEMI-INSULATING GROUP III	China	Pending	201110061625.5	3/11/2011		
METAL NITRIDE AND METHOD OF	Cinna	Tenung	201110001025.5	3/11/2011		
MANUFACTURE		-				
SEMI-INSULATING GROUP III METAL	USA	Issued	13/041,199	3/4/2011	8,878,230	11/4/2014
NITRIDE AND METHOD OF MANUFACTURE	USA	ESSUEG	13/041,199	3/4/2011	0,070,230	11/4/2014
	USA	To and	12/65/ (15	10/10/2012	0.704.666	9/9/2017
APPARATUS FOR LARGE VOLUME	USA	Issued	13/656,615	10/19/2012	9,724,666	8/8/2017
AMMONOTHERMAL MANUFACTURE OF						
GALLIUM NITRIDE CRYSTALS AND						
METHODS OF USE		-	2.5.115.1.00.5	2/22/22/2	***********	*******
APPARATUS FOR LARGE VOLUME	USA	Pending	15/474,806	3/30/2017		
AMMONOTHERMAL MANUFACTURE OF						
GALLIUM NITRIDE CRYSTALS AND						
METHODS OF USE	********************	***************************************				***********
APPARATUS FOR LARGE VOLUME	USA	Pending	13/657,551	10/22/2012		
AMMONOTHERMAL MANUFACTURE OF						
GALLIUM NITRIDE CRYSTALS AND						
METHODS OF USE		ļ				
PROCESS FOR LARGE-SCALE	Japan	Issued	2013-117510	6/4/2013	5788433	8/7/2015
AMMONOTHERMAL MANUFACTURING OF					******	
SEMIPOLAR GALLIUM NITRIDE BOULES						
PROCESS FOR LARGE-SCALE	USA	Pending	13/908,836	6/3/2013		
AMMONOTHERMAL MANUFACTURING OF						
SEMIPOLAR GALLIUM NITRIDE BOULES						
ULTRAPURE MINERALIZERS AND METHODS	USA	Issued	14/033,107	9/20/2013	9,299,555	3/29/2016
FOR NITRIDE CRYSTAL GROWTH					7	
ULTRAPURE MINERALIZERS AND METHODS	Japan	Pending	2016-044917	3/8/2016		
FOR NITRIDE CRYSTAL GROWTH	1				*****	
LARGE AREA, LOW-DEFECT	USA	Issued	13/600,191	8/30/2012	9,404,197	8/2/2016
GALLIUM-CONTAINING NITRIDE		100000	25,000,151	10,00,2012	3,101,237	0,10,2010
CRYSTALS, METHOD OF MAKING, AND						
METHOD OF USE						
LARGE AREA, LOW-DEFECT	USA	Pending	15/226,552	8/2/2016		
GALLIUM-CONTAINING NITRIDE	USA	1 chang	1.012000,000	01212010		
CRYSTALS, METHOD OF MAKING, AND						
METHOD OF USE						
METHOD OF CSE METHOD FOR QUANTIFICATION OF	USA	Issued	14/013,753	8/29/2013	9,275,912	3/1/2016
EXTENDED DEFECTS IN	USA	ISSUEG	14/013,733	8/29/2013	9,273,312	3/1/2010
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GALLIUM-CONTAINING NITRIDE CRYSTALS		12	0010 040510	11/06/0010		
HIGH QUALITY GROUP-III METAL NITRIDE	Japan	Pending	2013-243510	11/26/2013		
CRYSTALS, METHODS OF MAKING, AND						
METHODS OF USE		ļ	1.1200 201	11/07/00	0.500.50	00.000.00
HIGH QUALITY GROUP-III METAL NITRIDE	USA	Issued	14/089,281	11/25/2013	9589792	03/07/2017
CRYSTALS, METHODS OF MAKING, AND						
METHODS OF USE		1	1	1	1	
				·	·	
LARGE AREA SEED CRYSTAL FOR	USA	Issued	14/249,708	4/10/2014	9650723	05/16/2017
	USA	Issued	14/249,708	4/10/2014	9650723	05/16/2017

TRANSPARENT GROUP ILL METAL NITRIDE AND METHOD OF MANUFACTURE	USA	Issued				01/10/2017
L			14/485,516	9/12/2014	9543392	01/10/2017
REUSABLE NITRIDE WAFER, METHOD OF MAKING, AND METHOD OF USE	USA	Issued	14/805,278	7/21/2015	9653554	05/16/2017
REUSABLE NITRIDE WAFER, METHOD OF MAKING, AND USE THEREOF	USA	Pending	15/596,728	5/16/2017		
METHOD AND SYSTEM FOR PREPARING POLYCRYSTALLINE GROUP III METAL NITRIDE	USA	Pending	15/011,266	1/29/2016		
PRESSURE RELEASE MECHANISM FOR CAPSULE AND METHOD OF USE WITH SUPERCRITICAL FLUIDS	USA	Pending	15/269,538	9/19/16		
PRESSURE VESSEL	JAPAN	Issued	2003-563702	11/22/2002	4451662	2/5/2010
IMPROVED PRESSURE VESSEL	GERMANY	Issued	-h	11/22/2002	•	10/12/2006
IMPROVED PRESSURE VESSEL	FRANCE	Issued	2789868.3	11/22/2002		8/30/2006
HIGH TEMPERATURE HIGH PRESSURE CAPSULE FOR PROCESSING MATERIALS IN SUPERCRITICAL FLUIDS	USA	Issued	09/683659	1/31/2002		10/24/2006
HIGH TEMPERATURE HIGH PRESSURE CAPSULE FOR PROCESSING MATERIALS IN SUPERCRITICAL FLUIDS	USA	Issued	11/010139	12/10/2004	7,625,446	12/1/2009
CRYSTALLINE COMPOSITION, DEVICE, AND ASSOCIATED METHOD	USA	Issued	11/313451	12/20/2005	8,039,412	10/18/2011
APPARATUS FOR MAKING CRYSTALLINE COMPOSITION	USA	Issued	11/313442	12/20/2005	7,942,970	5/17/2011
METHOD FOR MAKING CRYSTALLINE COMPOSITION	USA	Issued	11/313528	12/20/2005	7,935,382	5/3/2011
CRYSTALLINE COMPOSITION, DEVICE, AND ASSOCIATED METHOD	CHINA	Issued	200680053099.5	12/15/2006	101379227	6/12/2013
CRYSTALLINE COMPOSITION, DEVICE, AND ASSOCIATED METHOD	EUROPE	Pending	06845438.8	12/15/2006		
CRYSTALLINE COMPOSITION, DEVICE, AND ASSOCIATED METHOD	JAPAN	Issued	2008-547331	12/20/2005	5143016	2/13/2013
CRYSTALLINE COMPOSITION, DEVICE, AND ASSOCIATED METHOD	KOREA (SOUTH)	Issued	2008-7015178	12/20/2005	101351498	1/15/2014
CRYSTALLINE GALLIUM NITRIDE AND METHOD FOR FORMING CRYSTALLINE GALLIUM NITRIDE	USA	Issued	09/413446	10/6/1999	6,398,867	6/4/2002
CRYSTALLINE GALLIUM NITRIDE AND METHOD FOR FORMING CRYSTALLINE GALLIUM NITRIDE	FRANCE	Issued	967039.9	9/28/2000	1230005	1/3/2007
CRYSTALLINE GALLIUM NITRIDE AND METHOD FOR FORMING CRYSTALLINE GALLIUM NITRIDE	GERMANY	Issued	967039.9	9/28/2000	60032793	2/15/2007
CRYSTALLINE GALLIUM NITRIDE AND METHOD FOR FORMING CRYSTALLINE GALLIUM NITRIDE	NETHERLA NDS	Issued	967039.9	9/28/2000	1230005	1/3/2007
CRYSTALLINE GALLIUM NITRIDE AND METHOD FOR FORMING CRYSTALLINE GALLIUM NITRIDE	JAPAN	Issued	2001-527911	9/28/2000	4942270	5/30/2012
CRYSTALLINE GALLIUM NITRIDE AND METHOD FOR FORMING CRYSTALLINE GALLIUM NITRIDE	KOREA (SOUTH)	Issued	10-2002-7004411	9/28/2000	10-076201 90000	6/19/2007
HIGH PRESSURE/HIGH TEMPERATURE APPARATUS WITH IMPROVED TEMPERATURE CONTROL FOR CRYSTAL GROWTH	USA	Issued	10/699504	10/31/2003	7,101,433	9/5/2006
HIGH PRESSURE HIGH TEMPERATURE GROWTH OF CRYSTALLINE GROUP III METAL NITRIDES	USA	Issued	10/063164	3/27/2002	7,063,741	6/20/2006

HIGH PRESSURE HIGH TEMPERATURE	GERMANY	Issued	3709199.8	2/21/2003	EP1490537	4/13/2011
GROWTH OF CRYSTALLINE GROUP III	O.S. C.	200000	0.703.53.0		1	,, 1,5,2011
METAL NITRIDES					DE603367	
	VODE		20015015515	2 (21 (20)2	15	10/10/2010
HIGH PRESSURE HIGH TEMPERATURE GROWTH OF CRYSTALLINE GROUP III	KOREA (SOUTH)	Issued	20047015545	2/21/2003	100987850	10/13/2010
METAL NITRIDES	(800111)					
APPARATUS FOR PRODUCING SINGLE	USA	Issued	11/249896	10/13/2005	7.368.015	5/6/2008
CRYSTAL AND QUASI-SINGLE CRYSTAL,	0011	100000	11,2,555	10, 10, 2000	,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,	D, O, 2000
AND ASSOCIATED METHOD						
APPARATUS FOR PROCESSING MATERIALS	USA	Issued	11/042858	1/25/2005	7,704,324	4/27/2010
IN SUPERCRITICAL FLUIDS AND METHODS						
THEREOF	DITOGIANT	Y 1	2007122167	10/10/2005	2202000	C/07/0010
IMPROVED APPARATUS FOR HIGH TEMPERATURE HIGH PRESSURE	RUSSIAN FEDERAT	Issued	2007132167	10/19/2005	2393008	6/27/2010
PROCESSING	TEDERAI					
IMPROVED APPARATUS FOR HIGH	POLAND	Issued	EP05811853	10/19/2005	1846148	12/22/2010
TEMPERATURE HIGH PRESSURE						
PROCESSING						
IMPROVED APPARATUS FOR HIGH	NETHERLA	Issued	EP05811853	10/19/2005	1846148	12/22/2010
TEMPERATURE HIGH PRESSURE	NDS					
PROCESSING	CEDMANIX	T	EP05811853	10/10/2005	(02005025	2/3/2011
IMPROVED APPARATUS FOR HIGH TEMPERATURE HIGH PRESSURE	GERMANY	Issued	EP03811833	10/19/2003	602005025 533	2/3/2011
PROCESSING					223	
IMPROVED APPARATUS FOR HIGH	FRANCE	Issued	EP05811853	10/19/2005	1846148	12/22/2010
TEMPERATURE HIGH PRESSURE						
PROCESSING						
APPARATUS FOR PROCESSING MATERIALS	EUROPE	Pending	EP20100011809	10/19/2005		
IN SUPERCRITICAL FLUIDS		· ·	200,8000,18030,6	1040400	101150710	449.00044
IMPROVED APPARATUS FOR HIGH	CHINA	Issued	200580047233.6	10/19/2005	101163540	4/13/2011
TEMPERATURE HIGH PRESSURE PROCESSING						
HEATER, APPARATUS, AND ASSOCIATED	USA	Issued	11/521034	9/14/2006	7,705,276	4/27/2010
METHOD	0.5.1	100000	I I Carlo	771 772000	,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,	17 au 77 au 0 1 0
INCOMPRESSIBLE HEATER AND METHOD	CHINA	Issued	200610064789.2	11/30/2006	101146379	11/9/2011
FOR MAKING						
INCOMPRESSIBLE HEATER AND METHOD	FRANCE	Issued	EP06024819	11/30/2006	EP1901584	30/5/2016
FOR MAKING	***************************************	********	***************************************			
INCOMPRESSIBLE HEATER AND METHOD	POLAND	Issued	EP06024819	11/30/2006	EP1901584	30/5/2016
FOR MAKING HEATER, APPARATUS, AND ASSOCIATED	JAPAN	Issued	2006-323731	11/30/2006	5044202	10/10/2012
METHOD	JAFAN	ISSUCU	2000-323731	11/30/2000	3044202	10/10/2012
HEATER, APPARATUS, AND ASSOCIATED	KOREA	Issued	20060120252	11/30/2006	101310437	9/25/2013
METHOD	(SOUTH)		10000110101	11,50,1000		,, 1 0,10
METHOD FOR FORMING NITRIDE CRYSTALS	USA	Issued	11/973182	10/5/2007	7,642,122	1/5/2010
METHOD FOR FORMING NITRIDE CRYSTALS	JAPAN	Issued	2009-531469	10/5/2007	5480624	4/23/2014
METHOD FOR FORMING NITRIDE CRYSTALS	EUROPE	Granted	07852559.9	10/5/2007		
ETCHANT, METHOD OF ETCHING,	USA	Issued	11/167719	6/27/2005	7,527,742	5/5/2009
LAMINATE FORMED THEREBY, AND						
DEVICE SINTERED POLYCRYSTALLINE GALLIUM	T TO A	T	10/001575	11/0/0001	6 061 120	2/1/2005
NITRIDE AND ITS PRODUCTION	USA	Issued	10/001575	11/2/2001	6,861,130	3/1/2005
SINTERED POLYCRYSTALLINE GALLIUM	JAPAN	Issued	2003-543080	10/30/2002	4349907	10/21/2009
NITRIDE	O'THE THE	ESSMOO	2000 0 10000	10,00,000	10.12207	10,22,2000
SINTERED POLYCRYSTALLINE GALLIUM	CHINA	Issued	2821830.2	10/30/2002	1280182	10/18/2006
NITRIDE						
SINTERED POLYCRYSTALLINE GALLIUM	KOREA	Issued	10-2004-7006467	4/29/2004	10-090325	6/9/2009
NITRIDE	(SOUTH)	*************			1	
APPARATUS FOR PROCESSING MATERIALS	USA	Pending	13/812757	7/28/2011		
AT HIGH TEMPERATURES AND PRESSURES	<u> </u>	***************************************		<u> </u>		

APPARATUS FOR PROCESSING MATERIALS	JAPAN	Issued	2013521972	7/28/2011	5887344	2/19/2016
AT HIGH TEMPERATURES AND PRESSURES						
TRANSISTOR PATENT:	USA	Issued	10/329982	12/27/2002	8089097	01/03/2012
HOMOEPITAXIAL						
GALLIUM-NITRIDE-BASED ELECTRONIC						
DEVICES AND METHOD FOR PRODUCING						
SAME						l

RECORDED: 11/14/2017